



Atty. Dkt. No.	M#	Client Ref.
	306865	P-0393.010-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: LOWISCH et al.	
Appln. No.: 10/716,939	
Filing Date: November 20, 2003	
Examiner:	Group Art Unit: 2812

Date: March 26, 2004

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**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AM	AR 5,789,734	08/1998	TORIGOE et al.			
AM	BR 6,078,380	06/2000	TANIGUCHI et al.			
AM	CR 6,115,108	09/2000	CAPODIECI			
	DR					
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	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
AM	OR 1 251 402 A1	10/2002	EUROPE	BASELMANS et al.				
	PR							
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							
	WR							

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

AM	XR	Katsura OTAKI, "Asymmetric Properties of the Aerial Image in Extreme Ultraviolet Lithography," Jpn. J. Appl. Phys. 39:6819-6826 (2000)			
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

Examiner Alan Mathews

Date Considered: 5-3-2005

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office



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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: LOWISCH et al.

Appln. No.: 10/716,939

Filing Date: November 20, 2003

Date: May 4, 2004

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of

1

Examiner: NOT ASSIGNED

Group Art Unit: 2812

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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BR						
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DR						
ER						
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GR						
HR						
IR						
JR						
KR						
LR						
MR						

## FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
AM	NR 1 271 247 A1	01/2003	EUROPE	Van der Werf et al.				
	OR							
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	QR							
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## OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

AM	VR	Chen et al., "Simulation on a New Reflection Type Attenuated Phase Shifting Mask for Extreme Ultraviolet Lithography," SPIE, Vol. 3676, March 1999, pp. 578-586.				
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	XR					
	YR					
	ZR					
	AAR					

Examiner Alan Mathews

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